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Dispersed Ni nanoparticles stabilize silicon photoanodes for efficient and inexpensive sunlight-assisted water oxidation

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7 Dispersed Ni Nanoparticles Stabilize Silicon
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11 Photoanodes for Efficient and Inexpensive Sunlight-
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15 Assisted Water Oxidation
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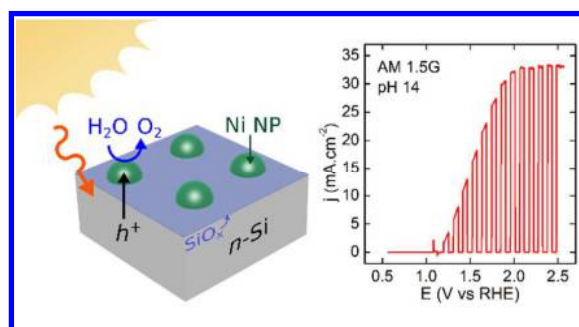
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ABSTRACT

Ni, electrodeposited on *n*-type Si from aqueous solutions, in the form of isolated or coalescent nanoparticles (NPs) protects the underlying and partially exposed Si from photocorrosion-induced electrical passivation. Such photoanodes, fabricated without the need of additional protecting layers, buried junction and high vacuum techniques, show a high photovoltage of ≈ 500 mV for the oxygen evolution reaction (OER), state-of-the-art photocurrents and faradaic efficiencies $>90\%$ under AM 1.5G illumination conditions at pH 14. Remarkably, these photoelectrodes are stable and can be operated at the light-limited catalytic current from 10 h to more than 40 h in 1 M NaOH. These findings demonstrate that robust and efficient Si-based photoanodes can be produced easily, which opens new opportunities for the implementation of low-cost Si-based monolithic photoelectrochemical cells for efficient solar fuel production.

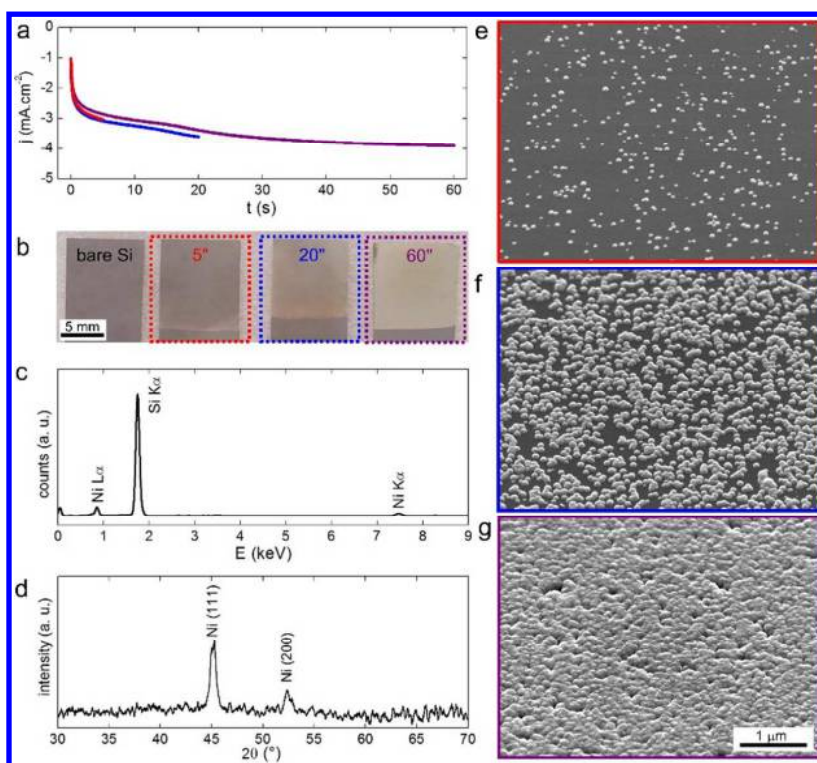
TOC GRAPHICS



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3 Carbon-free chemical fuels that can be produced from renewable sources are highly promising
4 energy vectors, essential for the development of a sustainable energy economy.¹ In this frame, H₂
5 is of particular interest because it provides a high energy density, it can be easily stored,
6 transported and readily used to power electrical devices. Alike photosynthesis, where photons are
7 converted into energy-rich molecules, sunlight energy can be converted in H₂ and O₂ using
8 photoelectrochemical water splitting cells (PECs), that are currently attracting tremendous
9 research efforts.²⁻⁷ Monolithic PECs are generally composed of a *p*-type semiconductor (*p*-SC)
10 and an *n*-type SC (*n*-SC) that are in intimate contact and immersed in an aqueous solution. Upon
11 sunlight absorption, photogenerated charge carriers are driven to the solid-liquid interface where
12 they react with water.²⁻⁷ Electrons generated in the *p*-SC reduce water to H₂ while holes,
13 generated in the *n*-SC, oxidize water to O₂ simultaneously. Silicon is considered as one of the
14 most attractive materials for manufacturing PEC photoelectrodes because of its abundance and
15 its wide use in microelectronic and photovoltaic industries.⁸ Moreover, it conveniently has a high
16 carrier mobility, a suitable electronic structure and an optimal band gap that allows absorbing all
17 the solar spectrum.⁸ Nevertheless, using Si as a photoanode material is very challenging mainly
18 because of two reasons: *i*) water oxidation is a four-electron process, which is sluggish at Si
19 surface and requires a substantial overpotential to occur and *ii*) Si is highly prone to
20 photocorrosion, and its oxidation to insulating SiO_x is the main process arising under anodic
21 polarization.⁸⁻¹⁰ The latter phenomenon is strongly pronounced in alkaline media, and induces
22 the quasi-spontaneous passivation of Si photoanodes when used for water splitting. This
23 technological issue had remained a deadlock for the development of Si monolithic PECs for the
24 last decades. Recently, tremendous progress has been made by employing thin film deposition
25 techniques such as physical vapor deposition (PVD) and atomic layer deposition (ALD) for
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3 coating Si with conformal single or multiple thin films that serve as protecting and/or catalytic
4 layers.⁸⁻¹¹ Ni and NiO_x are excellent coating materials as they provide corrosion resistance and a
5 high catalytic activity for the oxygen evolution reaction (OER) at high pH (see table S1).^{12,13} In
6 particular, Kenney *et al.* have firstly reported that e-beam evaporated thin Ni layers protect Si
7 photoanodes.¹⁴ Following this work, Ni-based alloys and oxides, sputtered on *n*-Si¹⁵ and *np*⁺-
8 Si¹⁶⁻¹⁸ junctions have demonstrated high performances for OER. Notably, Lewis' team has
9 demonstrated that layers of Ni¹⁹ and NiCrO_x,²⁰ sputtered on TiO₂-protected planar and
10 microstructured *np*⁺-Si junctions, were stable for periods of 100 h¹⁹ and 2200 h,²⁰ respectively, in
11 strongly alkaline media. Furthermore, a reactive sputter method has been developed for coating
12 Si surfaces with transparent NiO_x layers,²¹ that protect Si-based photoelectrodes for prolonged
13 water splitting.²² If these works constitute major breakthroughs for the implementation of
14 efficient and stable Si-based PECs, they all share the use of high vacuum techniques for the layer
15 deposition. Alternatives to sputtering and ALD would be interesting from a financial point of
16 view but also because they would open exciting possibilities in terms of layer composition and
17 morphologies. In this context, NiO_x layers, deposited by a sol-gel method on *n*-Si have a
18 catalytic activity towards OER at neutral²³ and alkaline pH.²⁴ Although electrodeposition has
19 been not much explored for this application so far, it is very attractive since it can be easily
20 implemented and it allows a precise control over the coating morphology. In this context, Nocera
21 *et al.* have reported the use of electrodeposited Co-based catalysts, operating at neutral pH on
22 Si.²⁵ Lately, Switzer's group has shown that inhomogeneous Co particles, electrodeposited on *n*-
23 Si surfaces allow to perform OER for 2 h at high pH and it has been very recently reported that
24 NiFe electrodeposited on *np*⁺-Si is highly effective for OER.²⁷ High interest is currently being
25 given to the understanding of Si interfaces coated with inhomogeneous co-catalysts layers. In
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3 particular, recent reports have shown that the photovoltages of these photoanodes are
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5 independent of the solution potential and suggested that the large barrier heights are caused by
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7 the presence of a native SiO_x layer and the inhomogeneous nature of the metal-insulator-
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9 semiconductor (MIS) structure that enhance the barrier height.^{27,28} However, Ni
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11 electrodeposition on *n*-Si was not employed so far to yield efficient photoanodes. In this work,
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13 we use electrodeposition to decorate *n*-Si surfaces with Ni co-catalysts and we demonstrate that
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15 this method allows to fabricate robust photoanodes for efficient photoelectrochemical water
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17 splitting.
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Figure 1. Characterization of the Ni-decorated surfaces. a) Chronoamperograms for Ni electrodeposition on hydrogenated *n*-Si. b) Photographs of bare and Ni-coated *n*-Si. c) EDS and d) XRD spectra of Ni-coated *n*-Si. e-g) SEM pictures showing the Ni deposits on *n*-Si (the

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3 surfaces were tilted by 45°). In these panels, data depicted or framed in red, blue and purple
4 correspond to the surfaces obtained for electrodeposition times of 5 s, 20 s and 60 s, respectively.
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9 In this work, Ni was deposited at -1.5 V vs KCl-saturated calomel electrode (SCE) on freshly
10 hydrogenated *n*-Si (100) from an aqueous solution containing Ni chloride and boric acid. The
11 potentiostatic method allows to conveniently control the amount of deposited material as well as
12 the morphology of the layer over time. Indeed, the chronoamperograms of Fig. 1a reveal the
13 evolution of the electrodeposition kinetics and show that the current density *j* decreased sharply
14 before stabilizing. This is consistent with the formation of nuclei that grow and reach
15 coalescence. The resulting coatings were homogeneous and could be observed with the naked
16 eye (Fig. 1b). Energy-dispersive X-ray spectroscopy (EDS) and X-ray diffraction (XRD)
17 measurements confirmed the presence of crystalline Ni on Si (Fig. 1c and 1d). Scanning electron
18 microscopy (SEM) images, shown in Fig. 1e-g (and Fig S1-3) indicated that 5 s electrodeposition
19 led to a film of randomly-dispersed Ni nanoparticles (Ni NPs) having a mean diameter of 59 ± 17
20 nm (Fig. S4). At 20 s, the Ni NPs grew further and the majority started to merge, creating NP
21 aggregates having a projected area in the range of 0.05 μm², while at 60 s they all coalesced,
22 yielding a deposit that can be considered as a film with a thickness of 68 ± 11 nm (Fig. S1d). The
23 photoelectrochemical performances of the so-fabricated surfaces were then tested in 1 M NaOH
24 (measured pH = 14), using simulated sunlight (AM 1.5G, 100 mW cm⁻²). First, we verified by
25 cyclic voltammetry (CV) that uncoated *n*-Si quickly passivated under these experimental
26 conditions, due to photocorrosion (Fig. S5). Before any experiments, the Ni-coated
27 photoelectrodes were cycled by performing several CV scans under illumination (typically, < 40)
28 until they reached a stable photocurrent curve (see Supporting Information and Fig. S8). Fig. 2
29 shows the CVs obtained for the coated Si surfaces, under illumination for *n*-Si and in the dark for
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n - and p^{++} -Si (note that the potential scale versus reversible hydrogen electrode (RHE), is plotted on the top of Fig. 2). In this work, unless specified, the cell resistance was intentionally uncompensated. In the dark, all currents were negligible (in the range of $1 \mu\text{A cm}^{-2}$), except for Ni-coated p^{++} -Si that is essentially behaving as a metal. In contrast, photocurrents densities in the mA cm^{-2} range were measured for Ni-coated n -Si under illumination.

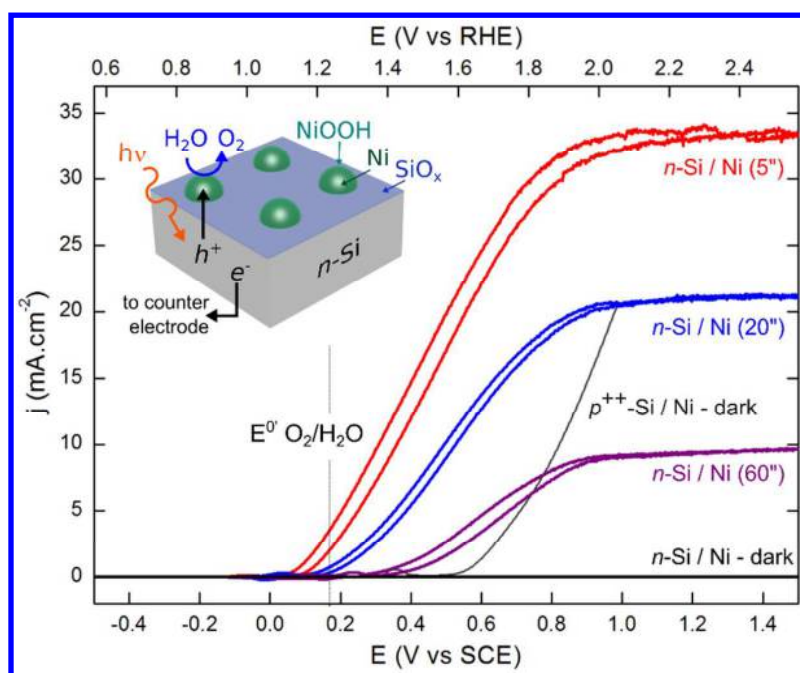


Figure 2. Photoelectrochemical water oxidation. CVs measured in the dark for n -Si decorated with Ni NPs (thick black line) and p^{++} -Si coated with Ni (thin black line) and under illumination (AM 1.5G, 100 mW cm^{-2}) for n -Si coated with Ni for 5 s (red line), 20 s (blue line) and 60 s (purple line); all the curves were recorded in 1 M NaOH at a sweep rate of 20 mV s^{-1} . Inset: scheme of the surface under illumination.

In all cases, a scan rate-dependent reversible redox wave ($\text{Ni}^{3+}/\text{Ni}^{2+}$) was first observed, corresponding to the oxidation of Ni hydroxide to NiOOH (Fig. S6 and Fig. S11), generated at the Ni NP-electrolyte interface upon immersion in the alkaline solution and during the

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3 electrochemical cycling (note that NiOOH is the catalytically active species for OER).^{12,29} The
4 determination of the charge under the oxidation peak (shown in Fig. S11 for an electrodeposition
5 time of 5 s), as compared with the NP density and average diameter (Fig. S4), allowed to
6 estimate that about one fifth of the Ni atoms were catalytically-active. This wave was followed,
7 at potential ~100 mV more positive than its cathodic peak (E_{pc}), by the much larger OER
8 photocurrent. Table S2 gathers the photoelectrochemical parameters as a function of the doping
9 type and the Ni amount. From these data, it can be clearly observed that every *n*-Si photoanode
10 exhibited a negative shift of onset potential with respect to the Ni-coated p^{++} -Si anode. The
11 photovoltage and the maximum photocurrent density j_{max} were clearly Ni-dependent and
12 increased with a decreasing amount of electrodeposited Ni. As it can be seen in Fig. 2 and Fig
13 S15, the decoration with isolated Ni NPs (Fig. 1e) provided the highest photovoltage and
14 photocurrent density. This photovoltage of 0.5 V is very close to the one reported for conformal
15 ultrathin Ni coatings prepared by e-beam evaporation on *n*-Si photoanodes without buried
16 junctions.¹⁴ The photocurrent of 33 mA cm⁻² is in the same range than the one obtained for
17 sputtered Ni-based coatings on np^{+} -Si junctions^{21,22} and electrodeposited Co on *n*-Si at
18 comparable pH.²⁶ The flatband potentials (E_{fb}) were comprised between -0.55 and -0.60 V vs
19 SCE (Fig S7), which is also in good agreement with the values reported for sputtered Ni films.¹⁴
20 The best electrode generated a photocurrent density of 3.5 mA cm⁻² at the O₂/H₂O formal
21 potential, corresponding to 16.5 mA cm⁻² when the cell resistance was compensated, as shown in
22 Fig. S16. The stability of the photoanodes was then evaluated by chronoamperometry (CA) at +1
23 V vs SCE in the same conditions during a prolonged time. Fig. 3a shows the photocurrent
24 evolution over time for the three different coatings. First, we note that all photocurrents obtained
25 in these experiments were very close to those previously observed in the CVs of Fig. 2. All the
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photoanodes maintained at least 70 % of their initial j_{max} over periods longer than 10 h, which is much higher than the durations previously reported at this pH for coatings electrodeposited on *n*-Si surfaces (Table S1).^{25,26}

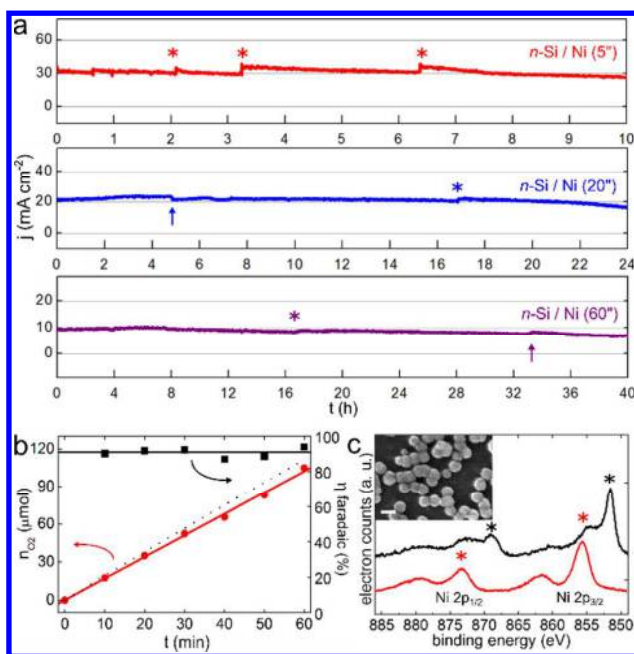


Figure 3. Stability and faradaic efficiency of the photoanodes. a) CAs obtained during prolonged photoelectrolysis in 1 M NaOH under AM 1.5G illumination at +1 V vs SCE for *n*-Si surfaces coated with Ni that was electrodeposited for 5 s (red), 20 s (blue) and 60 s (purple). The asterisks indicate when bubbles were removed from the surface, arrows indicate when the electrolysis was stopped and the photoelectrodes were dried and stored overnight. b) Number of moles of O₂ produced (red disks are experimental data and the red line is a linear fit) during a preparative electrolysis at +1 V vs SCE using a *n*-Si surface coated with Ni for 5 s (see SI for more details). The black dotted line is the theoretical amount of O₂, the black squares and the black line are the faradaic efficiencies and its average value, respectively. c) XPS spectra of the Ni 2p region for the *n*-Si surface coated with Ni for 20 s; after preparation (black line) and after \approx 25 h of electrolysis (red line). The black asterisks indicate Ni⁰ peaks and the red asterisks indicate Ni

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3 oxides peaks (more information on the spectra is provided in the SI). Inset: SEM picture showing
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6 the corresponding surface after electrolysis, the scale bar corresponds to 100 nm.
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11 These data clearly demonstrate that our photoanodes are particularly robust, even if the Ni
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13 deposits are not conformal. This is also shown by the fact that they maintained their activity after
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15 being stored in air (ambient conditions) overnight when the electrolysis was stopped. Such a
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17 stability was unexpected because, in the case of our best-performing photoanodes, most of the Si
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19 is in contact with the solution and therefore passivated with a SiO_x layer. X-ray photoelectron
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21 spectroscopy (XPS), confirmed the presence of oxygen on the freshly prepared surface and its
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23 significant increase after electrolysis (Fig. S13), suggesting that the Si surface is initially covered
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25 by a SiO_x layer that grows during the anodic polarization. Therefore, the photocatalytic
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27 performances and the stability seem related to the generation of an effective inhomogeneous
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29 metal-insulator-semiconductor (MIS) structure (Ni-SiO_x-Si).^{8,26} Interestingly, we clearly observe
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31 that the stability is enhanced with an increasing amount of Ni, showing that thicker and denser
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33 Ni coatings decrease the photocorrosion kinetics by protecting underlying Si from the oxidative
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35 solution. However, the stability is increased at the expense of the photocurrent density and
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37 photovoltage (Table S2). Like previously reported for electrodeposited discontinuous Co films²⁶
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39 and evaporated Ni layers behaving as inhomogeneous buried junctions,²⁸ thicker catalytic layers
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41 led, in our case, to weaker light-limited photocurrents and photovoltages.
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49 Gas chromatography (GC) confirmed that the produced gas was O₂. The best photoanode
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51 configuration (5 s electrodeposition) was tested by additional electrolyses in a Hoffman cell,
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53 which allowed measuring the volume of produced O₂ (see the SI for details). Fig. 3b shows that
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55 the photoelectrode produced O₂ at a rate of 4.5 μmol min⁻¹ cm⁻², which corresponds to a faradaic
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3 efficiency higher than >90 %, this was also confirmed by another set of experiments described in
4 the supporting information (see the SI and Fig. S10). Based on the amount of O₂ produced in Fig.
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6 3b and the number of active Ni sites determined by measuring the charge under the Ni³⁺/Ni²⁺
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8 wave of the CV (shown in Fig. S11), we calculated a turnover frequency (TOF) of 1.14 × 10⁵ h⁻¹
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10 (see supporting information for more details). Most of the electrodeposited Ni was still present
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12 on the surface after ≈25 h of electrolysis, as shown by SEM and XPS (Fig. 3c and in Fig. S12),
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14 which demonstrates the robustness of the interaction between the Ni NPs and the Si surface.
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20 In conclusion, we have demonstrated that *n*-Si surfaces coated with electrodeposited Ni can be
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22 used as efficient photoanodes with faradaic yields >90 % in strongly alkaline pH. The best
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24 performances in terms of photovoltage, onset potential and photocurrent density are in the same
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26 range than the one reported for more complicated thin layer processes on *n*-Si (table S1) and
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28 were obtained for randomly-dispersed Ni NPs, which led to a stability of 10 h at the light-limited
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30 photocurrent density (33 mA cm⁻²). We have shown that stability can be extended to 40 h by
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32 increasing the amount of Ni on the surface, which is detrimental to the photovoltage and
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34 photocurrent. Moreover, we have demonstrated that Ni coverage can be finely controlled by
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36 electrodeposition, which makes it a powerful tool for tuning the photoelectrode activity. These
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38 results show that cheap and reliable photoanodes can be simply fabricated without the need of
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40 high vacuum techniques. We anticipate that the performances reported here will be soon further
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42 improved by employing surface texturing³⁰ and buried *np*⁺ junctions. Electrodeposition could be
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44 beneficially used to improve the electrode design, for instance, by tuning the morphology of the
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46 Ni nanocatalysts, additionally, these surfaces may be appealing structures for studying
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48 fundamental phenomena taking place at Si-based photoanodes.
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3 ASSOCIATED CONTENT
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6 **Supporting Information.** The Supporting Information containing the experimental procedure
7 and the supplementary figures and tables is available free of charge on the ACS Publications
8 website.
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14 AUTHOR INFORMATION

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21 **Notes**

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23 The authors declare no competing financial interest.
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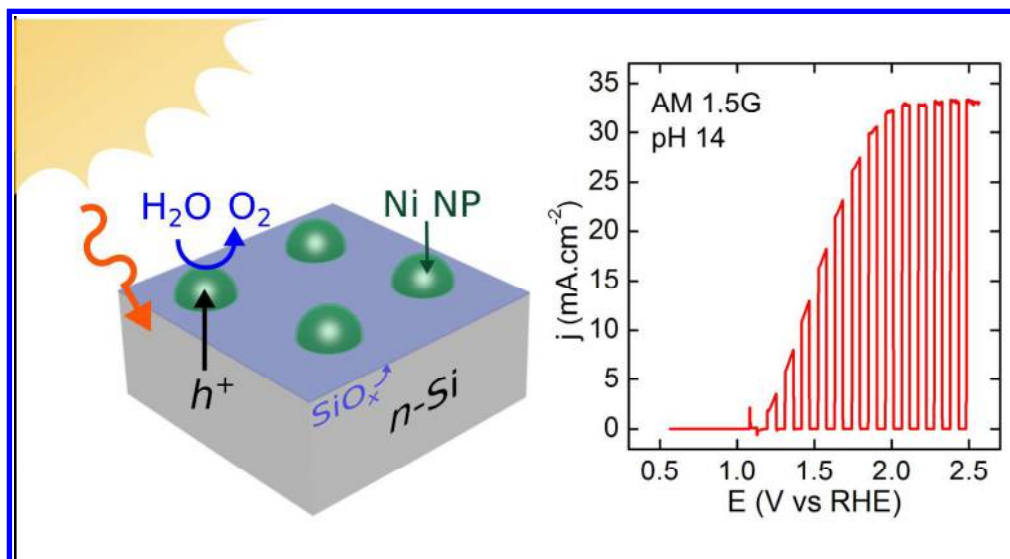
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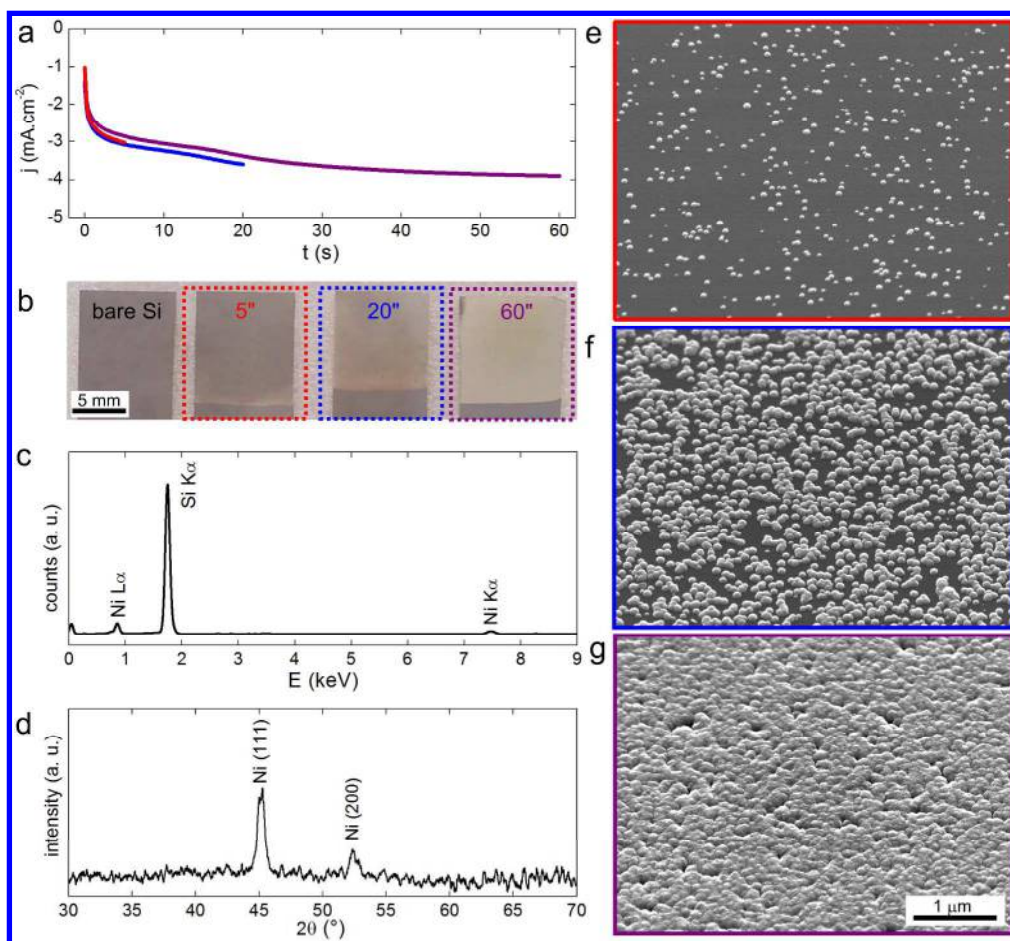


Figure 1. Characterization of the Ni-decorated surfaces. a) Chronoamperograms for Ni electrodeposition on hydrogenated n-Si. b) Photographs of bare and Ni-coated n-Si. c) EDS and d) XRD spectra of Ni-coated n-Si. e-g) SEM pictures showing the Ni deposits on n-Si (the surfaces were tilted by 45°). In these panels, data depicted or framed in red, blue and purple correspond to the surfaces obtained for electrodeposition times of 5 s, 20 s and 60 s, respectively.

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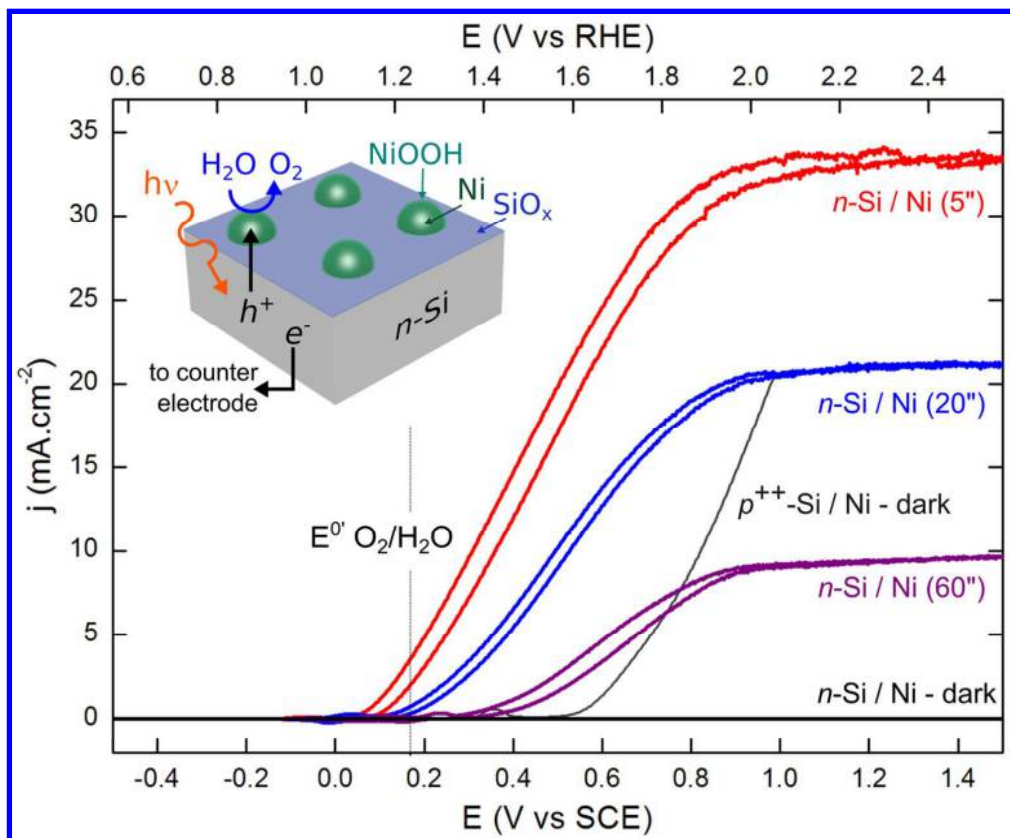


Figure 2. Photoelectrochemical water oxidation. CVs measured in the dark for n -Si decorated with Ni NPs (thick black line) and p^{++} -Si coated with Ni (thin black line) and under illumination (AM 1.5G, 100 mW cm⁻²) for n -Si coated with Ni for 5 s (red line), 20 s (blue line) and 60 s (purple line); all the curves were recorded in 1 M NaOH at a sweep rate of 20 mV s⁻¹. Inset: scheme of the surface under illumination.

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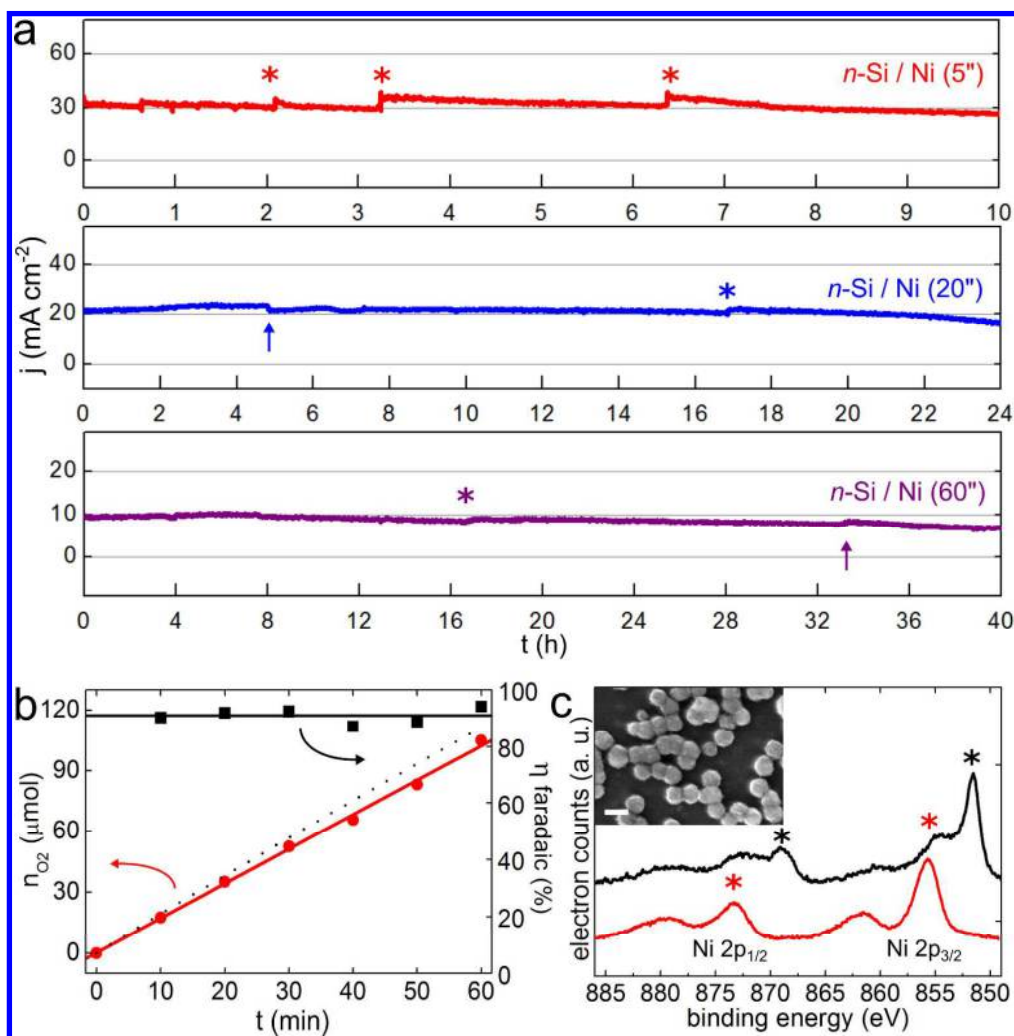


Figure 3. Stability and faradaic efficiency of the photoanodes. a) CAs obtained during prolonged photoelectrolysis in 1 M NaOH under AM 1.5G illumination at +1 V vs SCE for n-Si surfaces coated with Ni that was electrodeposited for 5 s (red), 20 s (blue) and 60 s (purple). The asterisks indicate when bubbles were removed from the surface, arrows indicate when the electrolysis was stopped and the photoelectrodes were dried and stored overnight. b) Number of moles of O₂ produced (red disks are experimental data and the red line is a linear fit) during a preparative electrolysis at +1 V vs SCE using a n-Si surface coated with Ni for 5 s (see SI for more details). The black dotted line is the theoretical amount of O₂, the black squares and the black line are the faradaic efficiencies and its average value, respectively. c) XPS spectra of the Ni 2p region for the n-Si surface coated with Ni for 20 s; after preparation (black line) and after ≈ 25 h of electrolysis (red line). The black asterisks indicate NiO peaks and the red asterisks indicate Ni oxides peaks (more information on the spectra is provided in the SI). Inset: SEM picture showing the corresponding surface after electrolysis, the scale bar corresponds to 100 nm.

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